## **News Release**



November 13, 2024

JX Advanced Metals Corporation

## Operations Launched at TANIOBIS in Germany for the Development and Production of High-Purity Metal Compounds —Powering an Expansion in Our Portfolio of CVD and ALD Precursor Materials for Semiconductors—

TANIOBIS GmbH (CEO: Ishii Masafumi), a Group company of JX Advanced Metals Corporation (President: Hayashi Yoichi; "the Company"), has installed and begun operating facilities at its Goslar, Germany site that will enable the development and production of CVD and ALD precursor materials for next-generation semiconductors.

TANIOBIS's Laufenburg site in Germany is engaged in the development and production of a range of metal compounds, with a specialization in metal chlorides. Growth in demand for advanced semiconductors in recent years has spurred a surge in customer inquiries regarding high-purity CVD and ALD precursor materials utilized in the deposition of extremely thin film layers and etching of microscopic circuitry inside semiconductors. Given this backdrop, TANIOBIS has installed and begun operating a new facility at its TANIOBIS site in Goslar, in the interest of expanding its product portfolio through the development of a diverse array of new, high-purity metal alloys and meeting the growth in demand for these products with a framework capable of ensuring stable supplies. In addition, it plans to beef up its supply capacity and business sustainability by further expanding production capacity at the existing TANIOBIS facility in Laufenburg.

The JX Advanced Metals Group is working to make CVD and ALD precursor materials business a pillar of next-generation earnings in the Semiconductor Materials segment. In June of this year, the Company decided to invest in production and development facilities within the Chigasaki Plant Premises of Toho Titanium Co., Ltd. and in the Shirogane area of the Company's Hitachi Works, and we will further expand our product lineup in conjunction with this facility enhancement. In addition, the Group will harness the vast networks and expertise the Company has cultivated in the semiconductor field through its sputtering target business for the expansion of this business in CVD and ALD precursor materials group-wide.

As a global leader in materials for semiconductors and information and communications equipment, the JX Advanced Metals Group will continue to contribute to the advancement and evolution of a sustainable society through the development and supply of high-performance, highly functional advanced materials.

## **Reference:**

Press Release dated June 18, 2024: "<u>Decision to Increase Capacity for Full-Scale Production of CVD and ALD</u> <u>Materials for Next-Generation Semiconductors</u>"



TANIOBIS's Goslar site in Germany